

# Younghwan Lee

Mailing address: Engineering building 6-216, 77 Yongbong-ro,  
Buk-gu, Gwangju, Korea, 61186  
Email: yhlee@jnu.ac.kr  
Office: +82-62-530-1696



## CURRENT AFFILIATION

**Assistant professor** Chonnam National University, Materials Science and Engineering  
Mar. 2024 – present

## CAREER

**Postdoctoral researcher** Seoul National University, Materials Science and Engineering  
Prof. Min Hyuk Park's group  
Jun. 2022 – Feb. 2024

## EDUCATION

**Ph. D.** North Carolina State University, Materials Science and Engineering  
Advisor: Prof. Jacob L. Jones  
Thesis: Interface Engineering in Ferroelectric  $\text{Hf}_{0.5}\text{Zr}_{0.5}\text{O}_2$  thin films  
Aug. 2017 – May. 2022

**M. S.** Seoul National University, Materials Science and Engineering  
Advisor: Prof. Shinhoo Kang  
Thesis: Densification Behavior and Sintering Mechanism of  $\text{MgAl}_2\text{O}_4$   
with Small Addition of Alkaline Earth Metal Carbonates  
Mar. 2015 – Aug. 2017

**B. S.** Pusan National University, Materials Science and Engineering  
Advisor: Prof. Hongchae Park  
Mar. 2008 - Feb. 2015

## RESEARCH INTEREST (KEYWORD)

Ferroelectrics, X-ray Diffraction,  $\text{HfO}_2$ , Thin film, Atomic layer deposition, Electroceramics

## HONORS AND AWARDS

- Carolina Science Symposium 2021 (Nov. 11–12, 2021)
- Best overall oral prize (sponsored by AVS Mid-Atlantic)
  - ASM Hans Stadelmaier Award
  - NCSU Nanofabrication Facility Best Poster Award

Joint conference of the IEEE ISAF-PFM-ECAPD 2022 (Jun. 27 – Jul. 1, 2022)

- Finalist of Best Student Paper Award
- Carolina Science Symposium 2019 (Nov. 8, 2019)
- NCSU Nanofabrication Facility Best Poster Award

## PUBLICATIONS

---

### *Journal Papers*

1. **Lee, Y.**<sup>†</sup>, Kim, S. H.<sup>†</sup>, Jeong, H. W., Park, G. H., Lee, J., Kim, Y. Y., & Park, M. H. (2024). Mitigation of field-driven dynamic phase evolution in ferroelectric  $\text{Hf}_{0.5}\text{Zr}_{0.5}\text{O}_2$  films by adopting oxygen-supplying electrode. *Applied Surface Science*, 648, 158948. (<sup>†</sup>**co-1<sup>st</sup> author**)
2. Kim, S. H.<sup>†</sup>, **Lee, Y.**<sup>†</sup>, Lee, D. H.<sup>†</sup>, Park, G. H., Jeong, H. W., Yang, K., ... & Park, M. H. (2024). Depolarization mitigated in ferroelectric  $\text{Hf}_{0.5}\text{Zr}_{0.5}\text{O}_2$  ultrathin films (< 5 nm) on Si substrate by interface engineering. *Journal of Advanced Ceramics*. (<sup>†</sup>**co-1<sup>st</sup> author**)
3. Lee, J., Kim, S. H., Choi, H., Jeong, H. W., Yang, K., Park, J. Y., ... **Lee, Y.**<sup>\*</sup> & Park, M. H.<sup>\*</sup> (2024). Ferroelectricity of  $\text{Hf}_{0.5}\text{Zr}_{0.5}\text{O}_2$  Thin Film Induced at 350 °C by Thermally Accelerated Nucleation During Atomic Layer Deposition. *IEEE Transactions on Electron Devices*. (<sup>\*</sup>**co-corresponding author**)
4. Silva, J. P., Alcalá, R., Avci, U. E., Barrett, N., Bégon-Lours, L., Borg, M., ... & Schroeder, U. (2023). “Roadmap on ferroelectric hafnia-and zirconia-based materials and devices.” *APL Materials*, 11(8).
5. Lee, D. H., Park, G. H., Kim, S. H., Yang, K., Lee, J., Choi, H., ... & Park, M. H. (2023). Effect of Electrode Material on the Polarization Switching Kinetics of  $\text{Hf}_{0.5}\text{Zr}_{0.5}\text{O}_2$  film. *IEEE Electron Device Letters*.
6. Lee, D. H.<sup>†</sup>, **Lee, Y.**<sup>†</sup>, Cho, Y. H., Choi, H., Kim, S. H., & Park, M. H. (2023). Unveiled Ferroelectricity in Well-Known Non-Ferroelectric Materials and Their Semiconductor Applications. *Advanced Functional Materials*, 2303956. (<sup>†</sup>**co-1<sup>st</sup> author**)
7. Hsain, H. A.<sup>†</sup>, **Lee, Y.**<sup>†</sup>, Lomenzo, P. D., Alcalá, R., Xu, B., Mikolajick, T., ... & Jones, J. L. (2023). Wake-up free ferroelectric hafnia-zirconia capacitors fabricated via vacuum-maintaining atomic layer deposition. *Journal of Applied Physics*, 133(22). (<sup>†</sup>**co-1<sup>st</sup> author**)
8. **Lee, Y.**<sup>†</sup>, Jeong, H. W.<sup>†</sup>, Kim, S. H., Yang, K., & Park, M. H. (2023). Effect of stress on fluorite-structured ferroelectric thin films for semiconductor devices. *Materials Science in Semiconductor Processing*, 160, 107411. (<sup>†</sup>**co-1<sup>st</sup> author**)
9. Park, J. Y.<sup>†</sup>, Lee, D. H.<sup>†</sup>, Park, G. H., Lee, J., **Lee, Y.**<sup>\*</sup>, & Park, M. H.<sup>\*</sup> (2023). A perspective on the physical scaling down of hafnia-based ferroelectrics. *Nanotechnology*, 34(20), 202001. (<sup>\*</sup>**co-corresponding author**)
10. Yang, K.<sup>†</sup>, Kim, S. H.<sup>†</sup>, Jeong, H. W., Lee, D. H., Park, G. H., **Lee, Y.**<sup>\*</sup>, & Park, M. H.<sup>\*</sup> (2023). Perspective on Ferroelectric Devices: Lessons from Interfacial Chemistry. *Chemistry of Materials*, 35(6), 2219-2237 (<sup>\*</sup>**co-corresponding author**)
11. Hsain, H. A., **Lee, Y.**, Lancaster, S., Lomenzo, P. D., Xu, B., Mikolajick, T., ... & Jones, J. L. (2023). Reduced fatigue and leakage of ferroelectric TiN/ $\text{Hf}_{0.5}\text{Zr}_{0.5}\text{O}_2$ /TiN capacitors by thin alumina interlayers at the top or bottom interface. *Nanotechnology*, 34(12), 125703.

12. **Lee, Y.**, Broughton, R. A., Hsain, H. A., Song, S. K., Edgington, P. G., Horgan, M. D., ... & Jones, J. L. (2022). "The influence of crystallographic texture on structural and electrical properties in ferroelectric  $\text{Hf}_{0.5}\text{Zr}_{0.5}\text{O}_2$ ." *Journal of Applied Physics*, 132(24), 244103.
13. Hsain, H. A., **Lee, Y.**, Lancaster, S., Materano, M., Alcala, R., Xu, B., ... & Jones, J. L. (2022). "Role of Oxygen Source on Buried Interfaces in Atomic-Layer-Deposited Ferroelectric Hafnia-Zirconia Thin Films." *ACS Applied Materials & Interfaces*, 14(37), 42232-42244.
14. Payne, A., Alex Hsain, H., **Lee, Y.**, Strnad, N. A., Jones, J. L., & Hanrahan, B.\* (2022). "Thermal stability of antiferroelectric-like Al:  $\text{HfO}_2$  thin films with TiN or Pt electrodes." *Applied Physics Letters*, 120(23), 232901.
15. Schroeder, U., Mittmann, T., Materano, M., Lomenzo, P. D., Edgington, P., **Lee, Y. H.**, ... & Jones, J. L.\* (2022). "Temperature-Dependent Phase Transitions in  $\text{Hf}_x\text{Zr}_{1-x}\text{O}_2$  Mixed Oxides: Indications of a Proper Ferroelectric Material." *Advanced Electronic Materials*, 2200265.
16. Hsain, H. A., **Lee, Y.**, Materano, M., Mittmann, T., Payne, A., Mikolajick, T., ... & Jones, J. L.\* (2022). "Many routes to ferroelectric  $\text{HfO}_2$ : A review of current deposition methods." *Journal of Vacuum Science & Technology A: Vacuum, Surfaces, and Films*, 40(1), 010803.
17. Shekhawat, A., Hsain, H. A., **Lee, Y.**, Jones, J. L., & Moghaddam, S.\* (2021). "Effect of ferroelectric and interface films on the tunneling electroresistance of the  $\text{Al}_2\text{O}_3/\text{Hf}_{0.5}\text{Zr}_{0.5}\text{O}_2$  based ferroelectric tunnel junctions." *Nanotechnology*, 32(48), 485204.
18. Lee, D. H.†, **Lee, Y.†**, Yang, K., Park, J. Y., Kim, S. H., Reddy, P. R. S., ... & Park, M. H.\* (2021). "Domains and domain dynamics in fluorite-structured ferroelectrics." *Applied Physics Reviews*, 8(2), 021312. (†**co-1<sup>st</sup> author**)
19. **Lee, Y.**, Alex Hsain, H., Fields, S. S., Jaszewski, S. T., Horgan, M. D., Edgington, P. G., ... & Jones, J. L.\* (2021). "Unexpectedly large remanent polarization of  $\text{Hf}_{0.5}\text{Zr}_{0.5}\text{O}_2$  metal–ferroelectric–metal capacitor fabricated without breaking vacuum." *Applied Physics Letters*, 118(1), 012903.
20. Park, J. Y.†, Yang, K.†, Lee, D. H.†, Kim, S. H.†, **Lee, Y.**, Reddy, P. S., ... & Park, M. H.\* (2020). "A perspective on semiconductor devices based on fluorite-structured ferroelectrics from the materials–device integration perspective." *Journal of Applied Physics*, 128(24), 240904.
21. Hsain, H. A., **Lee, Y.**, Parsons, G., & Jones, J. L.\* (2020). "Compositional dependence of crystallization temperatures and phase evolution in hafnia-zirconia ( $\text{Hf}_x\text{Zr}_{1-x}\text{O}_2$  thin films)." *Applied Physics Letters*, 116(19), 192901.
22. Strader, P., **Lee, Y.**, Teska, P., Li, X., & Jones, J. L.\* (2019). "Approaches for characterizing surfaces damaged by disinfection in healthcare." *Nano LIFE*, 9(04), 1950002.
23. Nam, S., Lee, M., Kim, B. N., **Lee, Y.**, & Kang, S.\* (2017). "Morphology controlled Co-precipitation method for nano structured transparent  $\text{MgAl}_2\text{O}_4$ ." *Ceramics International*, 43(17), 15352-15359.

## **RESEARCH PROJECTS**

---

Developing emerging neuromorphic synapse devices based on Ferroelectric Tunneling Junctions (FTJs) using fluorite-structured ferroelectric thin films (**principal investigator**)

- Amount: \$ ~150 k (180 million won)
- Period: 2022.9.1–2025.8.31 (terminated at 2024.2.29 due to change of affiliation)
- Grant No.: 2022R1A6A3A0108683211

## **CONFERENCES**

---

### ***Oral Presentation***

Korean Conference on Semiconductors 2024 (Jan. 24 – 26, 2024)

Joint conference of the IEEE ISAF-ISIF-PFM 2023 (Jul. 23 – 27, 2023)

Korean Conference on Semiconductors 2023 (Feb. 13 – 15, 2023)

Fall meeting of the Korean Ceramic Society 2022 (Oct. 26 – 28, 2022)

Materials Science & Technology 2022 (Oct. 9–12, 2022)

Joint conference of the IEEE ISAF-PFM-ECAPD 2022 (Jun. 27 – Jul. 1, 2022)

Carolina Science Symposium 2021 (Nov. 11–12, 2021)

Carolina Science Symposium 2020 (Nov. 12, 2020)

Joint Conference of the IEEE IFCS-ISAF (Jul. 19–23, 2020)

### ***Poster Presentation***

Carolina Science Symposium 2019 (Nov. 8, 2019)

Fall meeting of the Korean Ceramic Society 2016 (Nov. 23–25, 2016)

## **REFERENCES**

---

Available upon request.